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Conference Presentations :

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2. Kittipong Tantisantisom, Chanwit Chityuttakan, Sojiphong Chatraphorn and Kajornyod Yoodee, "Electrical and Optical properties of Gallium-Doped Zinc Oxide Thin Films Prepared by RF Magnetron Sputtering", *30th Congress on Science and Technology of Thailand (STT 2004)*, Impact Exhibition and Convention Center, Muang Thong Thani, Bangkok, Thailand, October 19-21, (2004).

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